

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

Application No. : 10/040,042  
Applicant : Wei-Yu Su  
Filed : November 7, 2001  
TC/A.U. : 1746  
Confirmation No. : 1835  
Title : Method for Reduction of Photomask Defects  
Examiner : El Arini, Zeinab  
Attorney Docket No : N1085-90003  
Customer No. : 08933

Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

Sir:

**AMENDMENT AND RESPONSE UNDER 37 CFR 1.116(a)**

In response to the Office Action of October 3, 2006, please amend the above-identified application as follows:

**Amendments to the Claims** are reflected in the listing of claims which begins on page 2 of this paper.

**Remarks** begin on page 7 of this paper.